L	Hits	Search Text	DB	Time stamp
Number 1	7136	(SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO;	2003/11/18 18:54
2	3883	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
3	626	microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 19:25
4	70	dimension\$4) ((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
5	7	<pre>microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:56
6	7	microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:57
7	7	focus\$4 (((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$\$) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
9	4	adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and (correct\$4 with (dos\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
10	2	or exposure)) ((((((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
12	4		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18

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13	4	((((((((SEM or (scanning adj electron adj microscop\$3)) and electron and	USPAT; US-PGPUB;	2003/11/18 19:07
1		(resist or photoresist)) and imag\$5) and	EPO; JPO;	ļ
		((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near	DERWENT;	
		width)) and (edge near2 bias\$4)) and	IBM_TDB	
		focus\$4) and patterns) and ((calculat\$5	1	l i
}	ł	or determin\$5 or measur\$6) with (chang\$4	1	i
	į	or bias\$4))) and ((correct\$4 or	}	}
		compensat\$5) with (dos\$4 or exposure))	j	j.
8	7	(((((((SEM or (scanning adj electron adj	USPAT;	2003/11/18
		microscop\$3)) and electron and (resist or	US-PGPUB;	19:08
	Ì	photoresist)) and imag\$5) and	EPO; JPO;	
	1	((critical\$4 or characteristic) near2	DERWENT;	
	}	dimension\$4)) and ((edge or pattern) near	IBM_TDB	j .
		width)) and (edge near2 bias\$4)) and	1	
		focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4		
		or bias\$4))	1	
11	7	((((((((SEM or (scanning adj electron	USPAT;	2003/11/18
	1	adj microscop\$3)) and electron and	US-PGPUB;	19:08
	į.	(resist or photoresist)) and imag\$5) and	EPO; JPO;	
		((critical\$4 or characteristic) near2	DERWENT;	
		dimension\$4)) and ((edge or pattern) near	IBM_TDB	
	İ	width)) and (edge near2 bias\$4)) and	1	i
	i	focus\$4) and patterns) and ((calculat\$5	ł	ì
	Į.	or determin\$5 or measur\$6) with (chang\$4		}
14	1545	or bias\$4))) and reference (((SEM or (scanning adj electron adj	USPAT;	2003/11/18
1 1 3	1343	microscop\$3)) and electron and (resist or	US-PGPUB;	19:24
		photoresist)) and imag\$5) and (electron	EPO; JPO;	13.21
	1	with imag\$5)	DERWENT;	{
	1		IBM_TDB	1
15	278	((((SEM or (scanning adj electron adj	USPĀT;	2003/11/18
	}	microscop\$3)) and electron and (resist or	US-PGPUB;	19:25
		photoresist)) and imag\$5) and (electron	EPO; JPO;	
		with imag\$5)) and ((critical\$4 or	DERWENT;	
16	36	characteristic) near2 dimension\$4)   (((((SEM or (scanning adj electron adj	IBM_TDB USPAT;	2003/11/18
10	36	microscop\$3)) and electron and (resist or	US-PGPUB;	19:27
ı		photoresist)) and imag\$5) and (electron	EPO; JPO;	
ı	ļ	with imag\$5)) and ((critical\$4 or	DERWENT;	ļ
	}	characteristic) near2 dimension\$4)) and	IBM TDB	
		((edge or pattern) near width)	_	
17	33	(((((SEM or (scanning adj electron adj	USPAT;	2003/11/18
	1	microscop\$3)) and electron and (resist or	US-PGPUB;	19:27
	1	photoresist)) and imag\$5) and (electron	EPO; JPO;	
	!	with imag\$5)) and ((critical\$4 or	DERWENT;	
		characteristic) near2 dimension\$4)) and	IBM_TDB	
	[	((edge or pattern) near width)) and monitor\$4		
	l	MOIIT COT 34	<u> </u>	L

L Number	Hits	Search Text	DB	Time stamp
18	12771	(SEM or (scanning adj electron adj microscop\$4)) and monitor\$4	USPAT; US-PGPUB; EPO; JPO;	2003/11/18 19:29
19	1407	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
20	171	(((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
21	158	((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
22	21	<pre>and pattern  (((((SEM or (scanning adj electron adj  microscop\$4)) and monitor\$4) and  (electron near5 imag\$5)) and ((critical\$4  or characteristic\$4) near2 dimension\$4))</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 19:31
23	14	and pattern) and (edge near2 width) ((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
24	9	microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:34
26	5	(exposure or dos\$4)) (((((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))) and ((((((((SEM or (scanning adj electron adj microscop\$4))) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:35

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27	5	<pre>(((((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
		<pre>((calculat\$4 or determin\$4) near5 (exposure or dos\$4)) ) and (((((((SEM or (scanning adj electron adj microscop\$4))) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4 )) and correct\$5</pre>		
28	5	<pre>((((((((((((((((((((((((((((((((((((</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:51
25	10	((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:50
29	5	((((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:49
30	10	<pre>((((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4) and correct\$5</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:50
31	10	((((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and model\$4) and correct\$5) and width	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:53

L Number	Hits	Search Text	DB	Time stamp
41	15192	(electron adj beam) and lithograph\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 21:05
42	79	((electron adj beam) and lithograph\$3) and (edge near width)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
43	27	(((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 21:11
44	16	<pre>((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 21:11
45	12	<pre>(pattern or portion)) (((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
46	11	or determin\$4) with (bias\$4 or deviat\$4)) ((((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
47	3	((((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
48	168	((electron adj beam) and lithograph\$3) and (edge near2 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
49	55	(((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
50	31	<pre>((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:17
51	16	<pre>(((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
52	14	<pre>((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12

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53	3	<pre>(((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
54	3	<pre>((((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and ((exposure or dos\$4) near2 energ\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
55	2		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:14
56	43036	imag\$5 with electron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
57	5735	(imag\$5 with electron) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
58	4907	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4	USPĀT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:15
59	87	<pre>(((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
60	74	<pre>(((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
61	39	<pre>(((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:18
62	9	<pre>((((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$5) with (change or deviation or bias\$4) with exposure)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18

64	4	(((((((imag\$5 with electron) and (resist	USPAT;	2003/11/18
(		or photoresist)) and pattern\$4) and	US-PGPUB;	21:21
	ĺ	((calculat\$5 or determin\$4) near5	EPO; JPO;	
1	İ	((characteristic or critical) near2	DERWENT;	
}		dimension\$3))) and width and edge) and	IBM_TDB	
]		((second or test or reference) near		
ļ		(pattern or portion))) and ((calculat\$5	 	
		or determin\$5) with (change or deviation		
j l	ĺ	or bias\$4) with exposure)) and (correct\$4		
		with exposure)) and model\$4	l I	
63	6	((((((imag\$5 with electron) and (resist	USPAT;	2003/11/18
	1	or photoresist)) and pattern\$4) and	US-PGPUB;	21:21
		((calculat\$5 or determin\$4) near5	EPO; JPO;	
		((characteristic or critical) near2	DERWENT;	
1	1	dimension(3))) and width and edge) and	IBM_TDB	
		((second or test or reference) near		
]	]	(pattern or portion))) and ((calculat\$5		
1		or determin\$5) with (change or deviation		
		or bias\$4) with exposure)) and (correct\$4		
L		with exposure)		<u> </u>

L Number	Hits	Search Text	DB	Time stamp
1	12065	imag\$5 near2 electron	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 22:17
2	2908	(imag\$5 near2 electron) and (resist or photoresist or mask or photomask)	IBM TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 22:18
3	165	((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 22:19
4	106	(((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 22:20
5	34	<pre>(edge-width)) ((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:35
6	16	<pre>((((((imag\$5 near2 electron) and (resist   or photoresist or mask or photomask)) and   ((characteristic or critical) near   dimension\$4)) and (edge and width or   (edge-width)) and (second near2 (pattern   or portion or area))) and ((calculat\$5 or   determin\$5) with (deviat\$4 or bias\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:24
7	16	<pre>((((((imag\$5 near2 electron) and (resist   or photoresist or mask or photomask)) and   ((characteristic or critical) near   dimension\$4)) and (edge and width or   (edge-width)) and (second near2 (pattern   or portion or area))) and ((calculat\$5 or   determin\$5) with (deviat\$4 or bias\$4))) and energ\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:25
8	2	<pre>((((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4) and (correct\$4 with</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:26
9	15	<pre>(exposure or energ\$4 or dos\$4)) (((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4) and (correct\$4 and (exposure or dos\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:26
10	15	or dos\$4))  (((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width)) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:27

11	15	<pre>((((((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:32
12	3	<pre>(resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
13	2	(resist or photoresist or mask or	USPAT; US-PGPUB;	2003/11/18 22:36
		photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)) and focus\$4) and (calculat\$4 with (deviat\$4 or bias\$4) with focus)	EPO; JPO; DERWENT; IBM_TDB	
14	360	<pre>(calculat\$4 with (dimension\$3 near (characteristic or critical)))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:35
15	49	((calculat\$4 with (dimension\$3 near (characteristic or critical)))) and (second near (pattern or portion or area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:36
16	4	<pre>(((calculat\$4 with (dimension\$3 near (characteristic or critical)))) and (second near (pattern or portion or area))) and ((calculat\$4 or determin\$5) with (deviat\$4 or bias\$4) with focus)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:39
17	4	<pre>(((calculat\$4 with (dimension\$3 near (characteristic or critical)))) and (second near (pattern or portion or area))) and ((calculat\$4 or determin\$5) with (deviat\$4 or bias\$4)) with focus)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:43
18	3160	((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:55
19	1191	((calculat\$4) with (change or deviat\$4 or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:55
20	1260	<pre>(((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure) ) and ((correct\$4 or compensat\$5) with exposure)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:56

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21	1087	((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with	USPAT; US-PGPUB;	2003/11/18 22:56
		exposure) ) and ((correct\$4 or	EPO; JPO;	22:56
		compensat\$5) with exposure)) and (model\$4	DERWENT;	j l
		or reference)	IBM TDB	
22	214	((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
	- 1	(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:57
		exposure) ) and ((correct\$4 or	EPO; JPO;	
		compensat\$5) with exposure)) and	DERWENT;	i i
	[	(model\$4)	IBM_TDB	
23	250	(((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:58
		exposure) ) and ((correct\$4 or	EPO; JPO;	
		compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or	DERWENT; IBM TDB	ļ .
	1	reference) near (pattern or portion))	I TEM_IDE	1
24	20	((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
2 1	] " "	(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:59
	]	exposure) ) and ((correct\$4 or	EPO; JPO;	
	[	compensat\$5) with exposure)) and (model\$4	DERWENT;	Ì
	1	or reference)) and ((second or test or	IBM_TDB	1
		reference) near (pattern or portion)))	_	
		and (calculat\$5 near4 dimension\$3)		
25	16	(((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:59
	]	<pre>exposure) ) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4</pre>	EPO; JPO; DERWENT;	}
		or reference)) and ((second or test or	IBM TDB	
		reference) near (pattern or portion)))	1511_155	i
		and (calculat\$5 near4 dimension\$3)) and		ł
		electron		
26	16	(((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
	[ [	(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:59
		exposure) ) and ((correct\$4 or	EPO; JPO;	}
		compensat\$5) with exposure)) and (model\$4	DERWENT;	1
		or reference)) and ((second or test or	IBM_TDB	
		reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and		
	1 1	electron) and pattern		
27	14	(((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
- '	] )	(change or deviat\$4 or bias\$4) with	US-PGPUB;	23:00
'	]	exposure) ) and ((correct\$4 or	EPO; JPO;	i -
		compensat\$5) with exposure)) and (model\$4	DERWENT;	,
		or reference)) and ((second or test or	IBM_TDB	
		reference) near (pattern or portion)))		]
		and (calculat\$5 near4 dimension\$3)) and		
1	[ _ [	electron) and pattern) and width	IICDAM.	2003/11/18
28	5	<pre>((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with</pre>	USPAT; US-PGPUB;	23:03
	1	exposure) ) and ((correct\$4 or	EPO; JPO;	23.00
		compensat\$5) with exposure)) and (model\$4	DERWENT;	1
	]	or reference)) and ((second or test or	IBM TDB	
	i 1	reference) near (pattern or portion)))	_	
		and (calculat\$5 near4 dimension\$3)) and	]	
	]	electron) and pattern) and width) and	J	I .
	_	(electron near5 imag\$5)		2002/11/20
29	5	(((((((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		<pre>(change or deviat\$4 or bias\$4) with exposure) ) and ((correct\$4 or</pre>	US-PGPUB; EPO; JPO;	23.03
		compensat\$5) with exposure)) and (model\$4	DERWENT;	1
		or reference)) and ((second or test or	IBM TDB	
	[	reference) near (pattern or portion)))		
		and (calculat\$5 near4 dimension\$3)) and		
		electron) and pattern) and width) and		
		(electron near5 imag\$5)) and (resist or		
		photoresist)	L	<u></u>

30	3	<pre>((((((((((((((((((((((((((((((((((((</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:05
31	5	<pre>(((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure) ) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:08
32	3	<pre>(((((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure) ) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and observ\$6</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:06
34	4	((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and ((characteristic or critical\$3) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:09
33	5	((((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and (characteristic or critical\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:26